

EPW
1742**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Koichi WATANABE et al.

Title: SPUTTERING TARGET

Appl. No.: 09/720,730

Filing Date: 12/29/2000

Examiner: S. Ip

Art Unit: 1742

STATEMENT OF SUBSTANCE OF INTERVIEW

Commissioner for Patents
PO Box 1450
Alexandria, Virginia 22313-1450

Sir:

Applicants appreciate the courtesies extended by Examiner Ip during the personal interview of July 20, 2005, which is of record in the application. During the interview, the existence of impurities Ta and oxygen in the sputtering target of Ohhashi (USP 5,693,203) were discussed. Applicants noted that the existence of impurities of TA and oxygen are inherent in Nb sputtering targets. Applicants also noted that the claimed dispersion (%) of Ta and oxygen is not inherent.

Applicants hereby petition for any extensions of time which may be required, and the Commissioner is hereby authorized to charge any additional fees which may be required regarding this application under 37 C.F.R. §§ 1.16-1.17, or credit any overpayment, to Deposit Account No. 19-0741. Should no proper payment be enclosed herewith, as by a check being in the wrong amount, unsigned, post-dated, otherwise improper or informal or even entirely missing, the Commissioner is authorized to charge the unpaid amount to Deposit Account No. 19-0741.

Respectfully submitted,

Date

August 1, 2005

By

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